FIG. 1

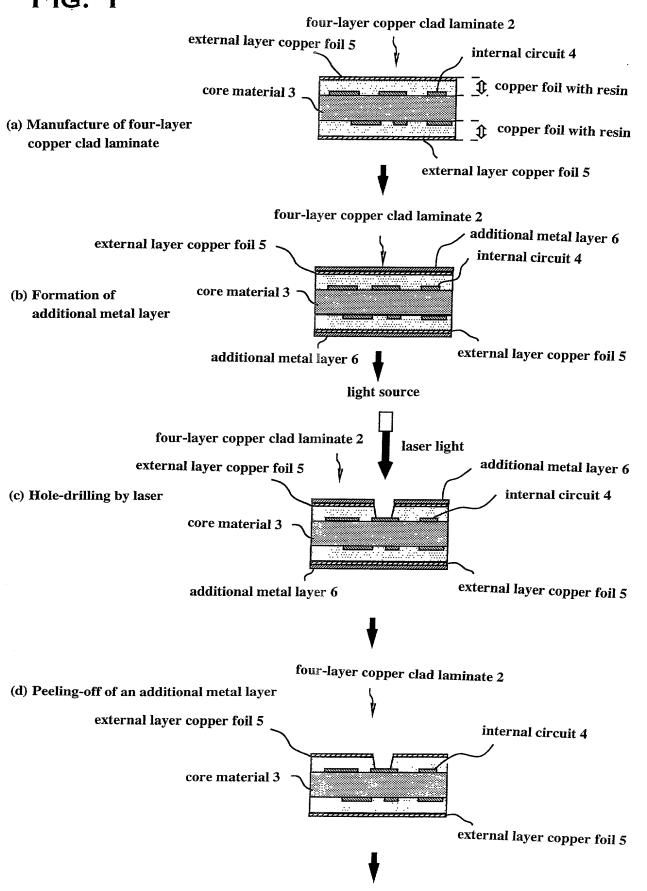
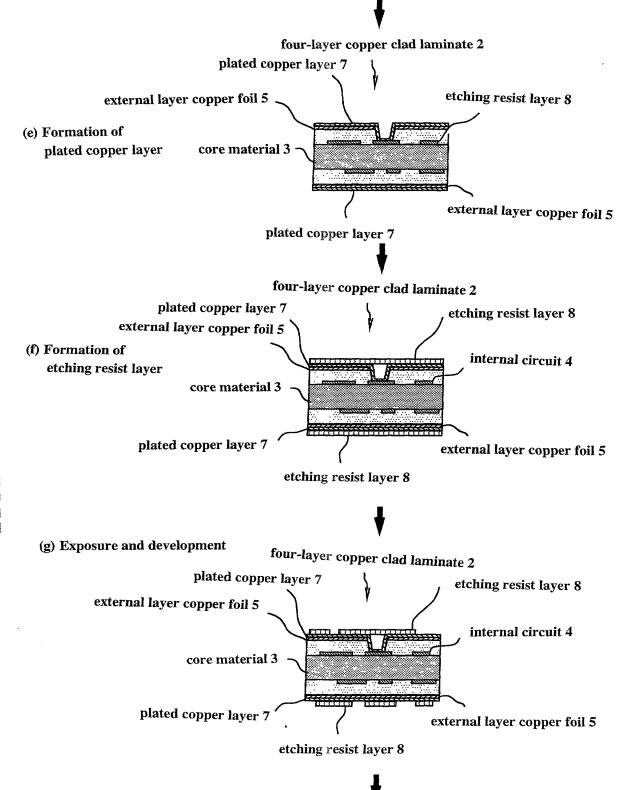
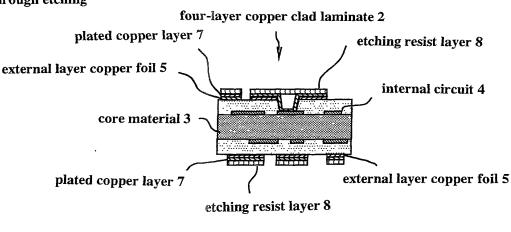
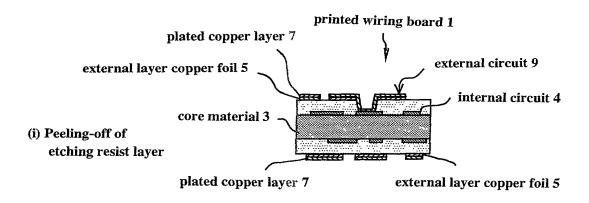


Fig. 2

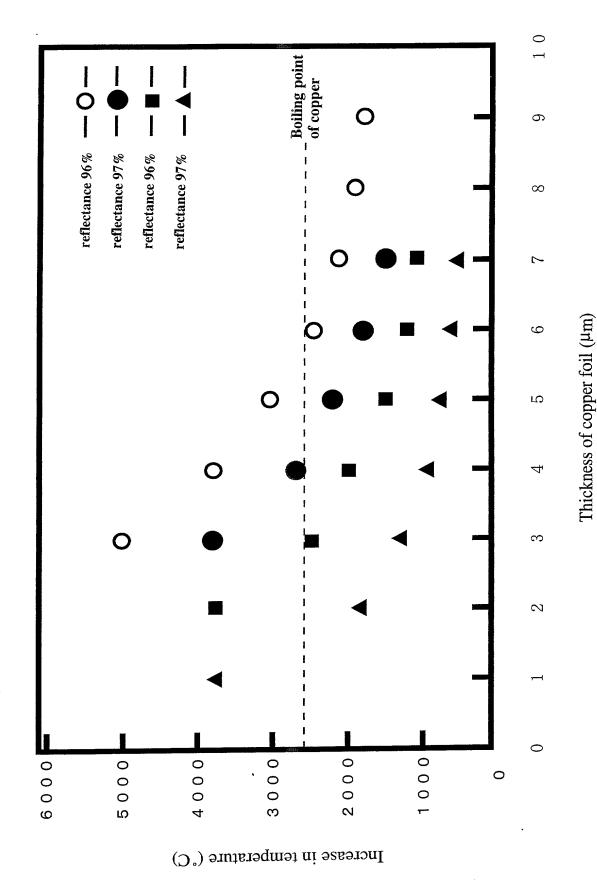


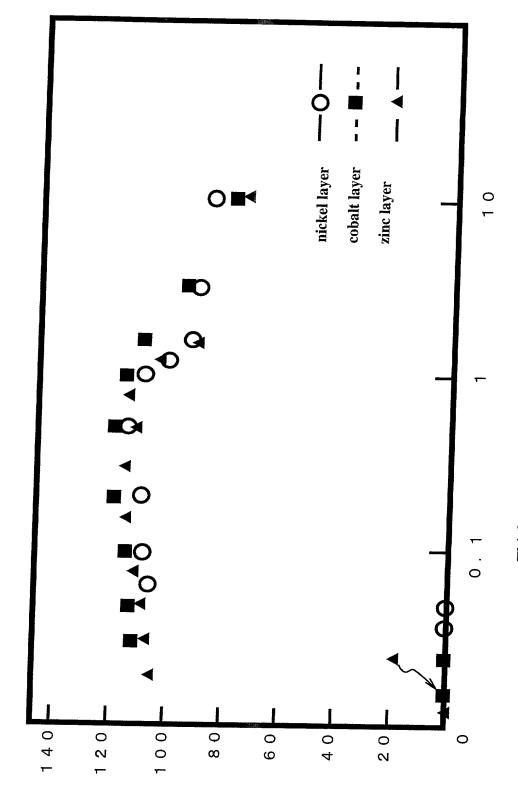
(h) Formation of a circuit through etching





-IG. 4



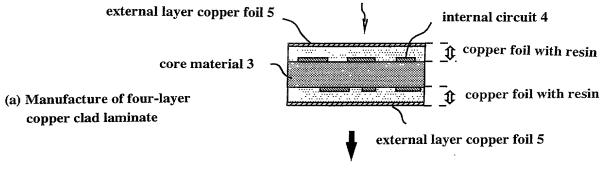


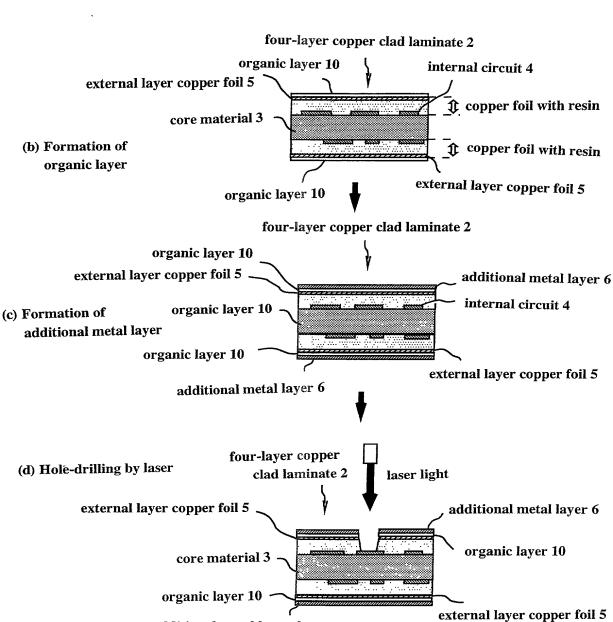
Diameter of a drilled hole $\$ $\mu_{\rm III}$

Thickness of an additional metal layer / μm

FIG. 6

four-layer copper clad laminate 2





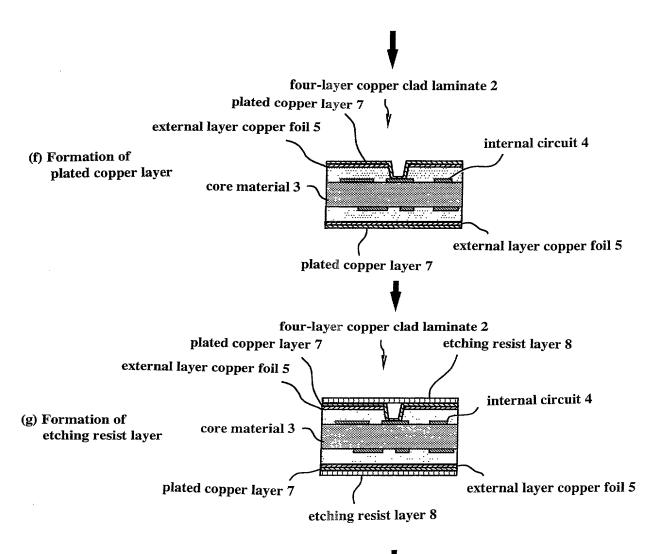
additional metal layer 6

four-layer copper clad laminate 2

external layer copper foil 5

(e) Peeling-off of additional metal layer and organic layer core material 3

external layer copper foil 5

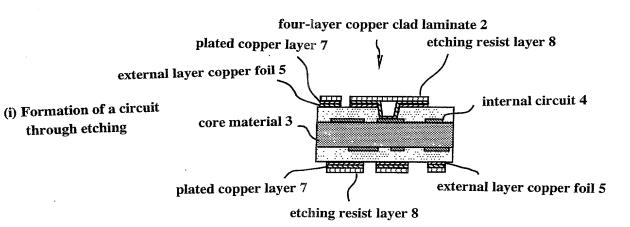




four-layer copper clad laminate 2
plated copper layer 7 etching resist layer 8
external layer copper foil 5
core material 3

(h) Exposure and development

plated copper layer 7 external layer copper foil 5





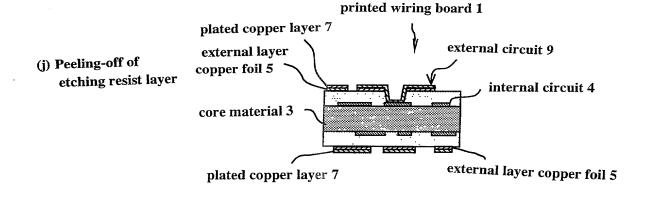


Fig. 9

external layer copper foil 5 core material 3 (a) Manufacture of four-layer copper clad laminate (b) copper foil with resin copper clad laminate external layer copper foil 5

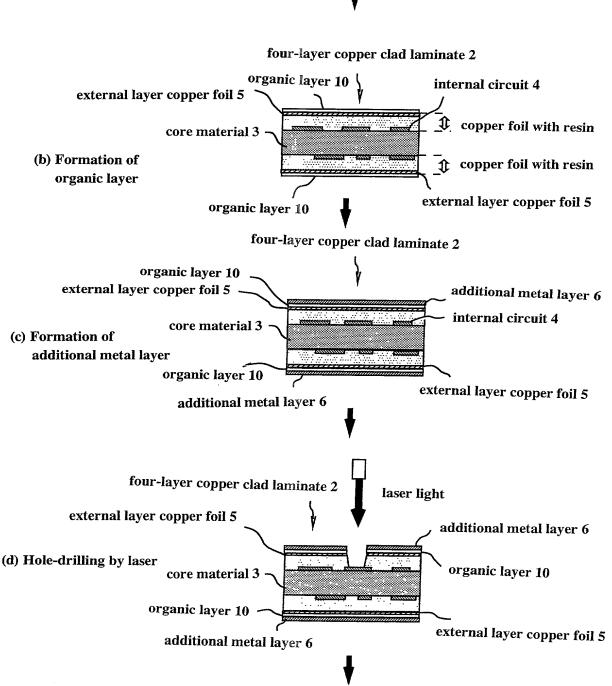


FIG. 10

four-layer copper clad laminate 2 plated copper layer 7 organic layer 10 additional metal layer 6 external layer copper foil 5 internal circuit 4 core material 3 (e) Formation of external layer plated copper layer copper foil 5 additional metal layer 6 organic layer 10 plated copper layer 7 four-layer copper clad laminate 2 plated copper layer 7 external layer copper foil 5 (f) Peeling-off of internal circuit 4 additional metal layer and organic layer core material 3 external layer copper foil 5 four-layer copper clad laminate 2 etching resist layer 8 plated copper layer 7 external layer copper foil 5 (g) Formation of internal circuit 4 etching resist layer core material 3 external layer copper foil 5

etching resist layer 8

FIG. 11

